

12 March 2004

Updated Search

09/834,308

L Number	Hits	Search Text	DB	Time stamp
-	35	136/\$.ccls. and (diffraction adj grating)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/07 12:24
-	50	136/252,255,256,259.ccls. and grating	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/07 15:01
-	4	136/252,255,256,259.ccls. and grating and (reactive adj ion adj etching)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/07 12:38
-	16	136/252,255,256,259.ccls. and (reactive adj ion adj etching)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/07 15:02
-	17	136/252,255,256,259,261.ccls. and (reactive adj ion adj etching)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/07 15:06
-	14	438/71,72,57,65.ccls. and (solar or photovoltaic or photodetector) and grating	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/07 15:09
-	4	(438/71,72,57,65.ccls. and (reactive adj ion adj etching)) and (438/71,72,57,65.ccls. and grating)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/07 15:16
-	32	438/71,72,57,65.ccls. and (reactive adj ion adj etching)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/07 15:36
-	3	zaidi.in. and (136/\$.ccls. or 257/\$.ccls. or 438/\$.ccls.)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/07 15:20
-	56	257/436,184,466.ccls. and (reactive adj ion adj etching)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/12 10:42
-	10	257/436,184,466.ccls. and (reactive adj ion adj etching) and grating	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/07 15:36
-	14	(136/\$.ccls. or 257/\$.ccls. or 438/\$.ccls.) and ruby.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 08:50
-	2853	(136/\$.ccls. or 257/\$.ccls. or 438/\$.ccls.) and (nitric adj acid)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 08:54

-	389	(136/\$.ccls. or 257/\$.ccls. or 438/\$.ccls.) and (nitric adj acid) and (chemical adj etching)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 08:55
-	102	(136/\$.ccls. or 257/\$.ccls. or 438/\$.ccls.) and (nitric adj acid) and (chemical adj etching) and (koh or (potassium adj hydroxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 08:56
-	29	(136/\$.ccls. or 257/\$.ccls. or 438/\$.ccls.) and (nitric adj acid) and (wet adj chemical adj etching) and (koh or (potassium adj hydroxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 08:59
-	9	(136/\$.ccls. or 257/\$.ccls. or 438/\$.ccls.) and (wet adj chemical adj etching) and ((potash or koh or (potassium adj hydroxide)) same (nitric adj acid))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 09:09
-	25	(US-6350945-\$ or US-5810945-\$ or US-4818337-\$ or US-4493942-\$ or US-4536608-\$ or US-4482779-\$ or US-4482778-\$ or US-4419533-\$ or US-4379944-\$ or US-6307145-\$ or US-4556790-\$ or US-4555622-\$ or US-4497974-\$ or US-4377722-\$ or US-4350561-\$ or US-4315097-\$ or US-6091021-\$ or US-5932114-\$ or US-5035770-\$ or US-6329296-\$ or US-4989972-\$ or US-5492859-\$ or US-5277748-\$).did. or (US-20010039101-\$).did. or (WO-9214270-\$).did.	USPAT; US-PGPUB; EPO	2002/03/08 12:36
-	2	((US-6350945-\$ or US-5810945-\$ or US-4818337-\$ or US-4493942-\$ or US-4536608-\$ or US-4482779-\$ or US-4482778-\$ or US-4419533-\$ or US-4379944-\$ or US-6307145-\$ or US-4556790-\$ or US-4555622-\$ or US-4497974-\$ or US-4377722-\$ or US-4350561-\$ or US-4315097-\$ or US-6091021-\$ or US-5932114-\$ or US-5035770-\$ or US-6329296-\$ or US-4989972-\$ or US-5492859-\$ or US-5277748-\$).did. or (US-20010039101-\$).did. or (WO-9214270-\$).did.) and blazed	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 12:51
-	1	136/252,255,256,259,261.ccls. and (gas adj source adj doping)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 12:54
-	1	136/\$.ccls. and (gas adj source adj doping)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 13:08
-	0	136/\$.ccls. and fahrenheit.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 13:13
-	163	136/252,255,256,259,261.ccls. and (ion adj implantation)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 13:13

-	90	136/252,255,256,259,261.ccls. and ((ion adj implantation) same junction)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 13:20
-	21	136/252,255,256,259,261.ccls. and ((annealing or annealed) with oxygen)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 13:21
-	27	(US-4989972-\$ or US-6350945-\$ or US-6329296-\$ or US-6091021-\$ or US-6307145-\$ or US-5932114-\$ or US-5810945-\$ or US-5492859-\$ or US-5277748-\$ or US-5035770-\$ or US-4818337-\$ or US-4556790-\$ or US-4555622-\$ or US-4497974-\$ or US-4536608-\$ or US-4493942-\$ or US-4482779-\$ or US-4482778-\$ or US-4419533-\$ or US-4379944-\$ or US-4377722-\$ or US-4350561-\$ or US-4315097-\$ or US-5792280-\$).did. or (US-20010039101-\$ or US-20020002992-\$).did. or (WO-9214270-\$).did.	USPAT; US-PGPUB; EPO	2002/03/08 14:07
-	2	((US-4989972-\$ or US-6350945-\$ or US-6329296-\$ or US-6091021-\$ or US-6307145-\$ or US-5932114-\$ or US-5810945-\$ or US-5492859-\$ or US-5277748-\$ or US-5035770-\$ or US-4818337-\$ or US-4556790-\$ or US-4555622-\$ or US-4497974-\$ or US-4536608-\$ or US-4493942-\$ or US-4482779-\$ or US-4482778-\$ or US-4419533-\$ or US-4379944-\$ or US-4377722-\$ or US-4350561-\$ or US-4315097-\$ or US-5792280-\$).did. or (US-20010039101-\$ or US-20020002992-\$).did. or (WO-9214270-\$).did.) and (surface near damage)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 14:16
-	0	6329296.URPN.	USPAT	2002/03/08 14:14
-	3	((US-4989972-\$ or US-6350945-\$ or US-6329296-\$ or US-6091021-\$ or US-6307145-\$ or US-5932114-\$ or US-5810945-\$ or US-5492859-\$ or US-5277748-\$ or US-5035770-\$ or US-4818337-\$ or US-4556790-\$ or US-4555622-\$ or US-4497974-\$ or US-4536608-\$ or US-4493942-\$ or US-4482779-\$ or US-4482778-\$ or US-4419533-\$ or US-4379944-\$ or US-4377722-\$ or US-4350561-\$ or US-4315097-\$ or US-5792280-\$).did. or (US-20010039101-\$ or US-20020002992-\$).did. or (WO-9214270-\$).did.) and (surface near3 damage)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 14:16

-	7	((US-4989972-\$ or US-6350945-\$ or US-6329296-\$ or US-6091021-\$ or US-6307145-\$ or US-5932114-\$ or US-5810945-\$ or US-5492859-\$ or US-5277748-\$ or US-5035770-\$ or US-4818337-\$ or US-4556790-\$ or US-4555622-\$ or US-4497974-\$ or US-4536608-\$ or US-4493942-\$ or US-4482779-\$ or US-4482778-\$ or US-4419533-\$ or US-4379944-\$ or US-4377722-\$ or US-4350561-\$ or US-4315097-\$ or US-5792280-\$).did. or (US-20010039101-\$ or US-20020002992-\$).did. or (WO-9214270-\$).did.) and damage	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 14:17
-	3	((US-4989972-\$ or US-6350945-\$ or US-6329296-\$ or US-6091021-\$ or US-6307145-\$ or US-5932114-\$ or US-5810945-\$ or US-5492859-\$ or US-5277748-\$ or US-5035770-\$ or US-4818337-\$ or US-4556790-\$ or US-4555622-\$ or US-4497974-\$ or US-4536608-\$ or US-4493942-\$ or US-4482779-\$ or US-4482778-\$ or US-4419533-\$ or US-4379944-\$ or US-4377722-\$ or US-4350561-\$ or US-4315097-\$ or US-5792280-\$).did. or (US-20010039101-\$ or US-20020002992-\$).did. or (WO-9214270-\$).did.) and (ion adj implantation) and phosphorous	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 15:03
-	27	(US-6350945-\$ or US-5810945-\$ or US-4818337-\$ or US-4536608-\$ or US-4493942-\$ or US-4482779-\$ or US-4482778-\$ or US-4419533-\$ or US-4379944-\$ or US-6307145-\$ or US-4556790-\$ or US-4555622-\$ or US-4497974-\$ or US-4377722-\$ or US-4350561-\$ or US-4315097-\$ or US-6091021-\$ or US-5932114-\$ or US-5035770-\$ or US-6329296-\$ or US-4989972-\$ or US-5792280-\$ or US-5492859-\$ or US-5277748-\$).did. or (US-20010039101-\$ or US-20020002992-\$).did. or (WO-9214270-\$).did.	USPAT; US-PGPUB; EPO	2002/03/08 15:46
-	26	((US-6350945-\$ or US-5810945-\$ or US-4818337-\$ or US-4536608-\$ or US-4493942-\$ or US-4482779-\$ or US-4482778-\$ or US-4419533-\$ or US-4379944-\$ or US-6307145-\$ or US-4556790-\$ or US-4555622-\$ or US-4497974-\$ or US-4377722-\$ or US-4350561-\$ or US-4315097-\$ or US-6091021-\$ or US-5932114-\$ or US-5035770-\$ or US-6329296-\$ or US-4989972-\$ or US-5792280-\$ or US-5492859-\$ or US-5277748-\$).did. or (US-20010039101-\$ or US-20020002992-\$).did. or (WO-9214270-\$).did.) and thickness	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 15:46

-	24	((US-6350945-\$ or US-5810945-\$ or US-4818337-\$ or US-4536608-\$ or US-4493942-\$ or US-4482779-\$ or US-4482778-\$ or US-4419533-\$ or US-4379944-\$ or US-6307145-\$ or US-4556790-\$ or US-4555622-\$ or US-4497974-\$ or US-4377722-\$ or US-4350561-\$ or US-4315097-\$ or US-6091021-\$ or US-5932114-\$ or US-5035770-\$ or US-6329296-\$ or US-4989972-\$ or US-5792280-\$ or US-5492859-\$ or US-5277748-\$).did. or (US-20010039101-\$ or US-20020002992-\$).did. or (WO-9214270-\$).did.) and thickness and silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 15:49
-	19	((US-6350945-\$ or US-5810945-\$ or US-4818337-\$ or US-4536608-\$ or US-4493942-\$ or US-4482779-\$ or US-4482778-\$ or US-4419533-\$ or US-4379944-\$ or US-6307145-\$ or US-4556790-\$ or US-4555622-\$ or US-4497974-\$ or US-4377722-\$ or US-4350561-\$ or US-4315097-\$ or US-6091021-\$ or US-5932114-\$ or US-5035770-\$ or US-6329296-\$ or US-4989972-\$ or US-5792280-\$ or US-5492859-\$ or US-5277748-\$).did. or (US-20010039101-\$ or US-20020002992-\$).did. or (WO-9214270-\$).did.) and (thickness same silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 15:49
-	17	((US-6350945-\$ or US-5810945-\$ or US-4818337-\$ or US-4536608-\$ or US-4493942-\$ or US-4482779-\$ or US-4482778-\$ or US-4419533-\$ or US-4379944-\$ or US-6307145-\$ or US-4556790-\$ or US-4555622-\$ or US-4497974-\$ or US-4377722-\$ or US-4350561-\$ or US-4315097-\$ or US-6091021-\$ or US-5932114-\$ or US-5035770-\$ or US-6329296-\$ or US-4989972-\$ or US-5792280-\$ or US-5492859-\$ or US-5277748-\$).did. or (US-20010039101-\$ or US-20020002992-\$).did. or (WO-9214270-\$).did.) and (thickness with silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/08 15:49
-	1	4419533.pn. and blazed	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/11 11:45
-	2	5792280.pn. and furnace	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/11 14:58
-	73	136/\$.ccls. and ((grating or diffraction) same order)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/08/26 11:29
-	10	136/\$.ccls. and ((grating near diffraction) same order)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/08/26 11:29

-	12132	136/\$.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/30 08:44
-	380	136/\$.ccls. and (diffractive or diffraction)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/30 08:59
-	90	136/\$.ccls. and ((first or second or zero\$3) adj order)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/30 08:44
-	10	(136/\$.ccls. and (diffractive or diffraction)) and (136/\$.ccls. and ((first or second or third or zero\$3) adj order))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/30 08:45
-	101	136/\$.ccls. and ((first or second or third or zero\$3) adj order)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/30 08:53
-	33	136/\$.ccls. and ((diffractive or diffraction) with order)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/06/30 10:12
-	4	216/58,83.ccls. and (diffraction adj (grate or grating))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 10:34
-	163	216/\$.ccls. and (diffraction adj (grate or grating))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 10:40
-	6	(216/\$.ccls. and (diffraction adj (grate or grating))) and (solar or photovoltaic)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 10:38
-	42	(216/\$.ccls. and (diffraction adj (grate or grating))) and (reactive adj ion adj etch\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 10:41
-	26	216/\$.ccls. and ((diffraction adj (grate or grating)) with (transmi\$7 or transparent))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 10:41
-	7	(216/\$.ccls. and ((diffraction adj (grate or grating)) with (transmi\$7 or transparent))) and (reactive adj ion adj etch\$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 11:25

-	343	136/\$.ccls. and (ion adj implantation)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 11:25
-	41	(136/\$.ccls. and (ion adj implantation)) and (diffraction or diffractive)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 11:25
-	3	(136/\$.ccls. and (ion adj implantation)) and ((diffraction or diffractive) adj grating)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 12:03
-	27	136/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean or remov\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 12:08
-	0	216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 12:08
-	27	136/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3 or remov\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 12:08
-	93	216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 12:18
-	76	(216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3))) and silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 12:15
-	17	(216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3))) not silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 12:16
-	76	(216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3))) not ((216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3))) not silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 12:16
-	0	((216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3))) not ((216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3))) not silicon) and ((clean\$5 or contamin\$7) with ((potassium adj hydroxide) or koh! or (wet adj chemical adj etch\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 12:19
-	180	216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3 or damag\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 12:19
-	33	(216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3 or damag\$3))) not silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 12:19

-	147	((216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3 or damag\$3))) not ((216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3 or damag\$3))) not silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 12:19
-	0	((216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3 or damag\$3))) not ((216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3 or damag\$3))) not silicon)) and ((clean\$5 or contamin\$7) with ((potassium adj hydroxide) or koh! or (wet adj chemical adj etch\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 12:19
-	2	((216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3 or damag\$3))) not ((216/\$.ccls. and ((rie or (reactive adj ion adj etch\$3)) with (contamin\$7 or clean\$3 or damag\$3))) not silicon)) and ((clean\$5 or contamin\$7 or damag\$4) with ((potassium adj hydroxide) or koh! or (wet adj chemical adj etch\$3)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 12:19
-	5	136/\$.ccls. and (grating adj solar adj cell)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/30 14:30
-	387	136/\$.ccls. and diffraction	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/30 14:12
-	140	(136/\$.ccls. and diffraction) not (ray adj diffraction)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/10/30 14:13
-	1	834308.apn.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/04 08:47
-	396	136/\$.ccls. and (diffraction)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/12 10:53
-	273	(136/\$.ccls. and (diffraction)) and "x-ray"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/12 10:32
-	123	(136/\$.ccls. and (diffraction)) not ((136/\$.ccls. and (diffraction)) and "x-ray")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/12 10:32
-	34	438/71,72,57,65.ccls. and grating	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/12 10:40

-	96	257/436,184,466.ccls. and (grating)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/12 10:42
-	101	136/\$.ccls. and (grating)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/12 10:53
-	60	(136/\$.ccls. and (grating)) not ((136/\$.ccls. and (diffraction)) not ((136/\$.ccls. and (diffraction)) and "x-ray"))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/03/12 10:53